

ELS-BODEN

Electron Beam Lithography System



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Acceleration 100kV × Single autoloader

High Performance Capabilities for High Resolution and High Throughput Applications

Features

Inherits traditional Elionix technology to meet user's requirements:

- 150kV / 125kV acceleration voltages, if ultra-fine patterns are most important.
- 100kV for common applications and a wide variety of requirements.
- 50kV for high speed production.


Available in 200mm and 300mm chambers:

- The first full 300mm square writing area in the marketplace.
- Sample holders from small pieces commonly used in basic research to 300mm wafers.
- Mask holders, for the 6025 and 9025 mask sizes, are also available.

Complete line of automatic loading systems:

- Single cassette autoloader, which is useful for research and development applications.
- Multiple cassette autoloader for small to medium volume production.
- Full lineup of robot loading systems

Specifications

Electron Gun	ZrO/W Thermal Field Emitter			
Acceleration voltage	50kV	100kV	125kV	150kV
Beam current	1nA ~ 800nA	20pA ~ 100nA	5pA ~ 100nA	5pA ~ 100nA
Min. beam spot size	2.8nm	1.8nm	1.7nm	1.5nm
Writing field size	1000μm□	1000μm□	500μm□	500μm□
Min. / Max. Field size	Min 100μm square Max (Option) 3000μm square			
Scan clock	Max 200MHz			
Min. beam position	0.1nm (at standard field)			
Max. sample size	200mm wafer / 300mm wafer			
Max. writing area	200mm square / 300mm square			
Loading system	Single autoloader Multi autoloader 300mm FOUF robot loader PEB robot loader			
Software	 Beam conditions Exposure schedule Pattern data converter Account management Python scripting			